

On Page 30, Fourth Full Paragraph, continuing on Page 31, First Partial Paragraph

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In the third embodiment, propylene glycol monomethyl ether acetate was used as the solvent for the organic material in the fabrication of the organic thin film 20. If the organic material for use in forming the organic thin film 20 contains at least one solvent of propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether, ethyl lactate, methyl methoxy propionate, ethyl ethoxy propionate, 2-heptanone, ethyl. pyruvate, diethylene glycol monomethyl ether, methyl cellosolve acetate, propylene glycol monoethyl ether acetate, ethyl methoxy propionate, methyl lactate and methyl pyruvate, the same effect as that obtained in this embodiment is provided. On the other hand, if cyclohexanone, diglyzme or methyl isobutyl ketone is used as the solvent for the organic material in forming the organic thin film 20, the same effect as that of the present embodiment was not provided and coating unevenness was recognized in the fabricated organic thin film.

IN THE CLAIMS:

Please amend claims 6 and 10 as follows:

6. (Amended) A method for fabricating an organic thin film comprising the steps of:
forming an undercoating film made of silicon nitride or silicon nitride oxide on a substrate;
wet-cleaning said undercoating film using a cleaning liquid; and
forming an organic thin film with a thickness of about 100nm or thinner on said undercoating film of which wet-cleaning has been completed by turning said substrate and supplying a liquid organic material onto said substrate;
wherein said organic material contains at least one solvent selected from the group consisting of propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether, ethyl lactate, methyl methoxy propionate, ethyl ethoxy propionate, 2-heptanone, ethyl pyruvate, diethylene glycol monomethyl ether, methyl cellosolve acetate, propylene glycol monoethyl ether acetate, ethyl methoxy propionate, methyl lactate and methyl pyruvate.

10. (Amended) A method for fabricating an organic thin film comprising the steps of:
forming an undercoating film made of silicon nitride or silicon nitride oxide on a

substrate;

irradiating far ultraviolet ray onto said undercoatilig film; and

forming an organic thin film with a thickness of about 100nm or thinner on said undercoating film onto which far ultraviolet ray has been irradiated, by turning said substrate and supplying a liquid organic material onto said substrate;

wherein said organic material contains at least one solvent selected from the group consisting of propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether, ethyl lactate, methyl methoxy propionate, ethyl ethoxy propionate, 2-heptanone, ethyl pyruvate, diethylene glycol monomethyl ether, methyl cellosolve acetate, propylene glycol monoethyl ether acetate, ethyl methoxy propionate, methyl lactate and methyl pyruvate.

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